IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

Applicant: Chae, et al. Case: APPM/8501/ETCH/DRIE

Serial No.: 10/706.902 Filed: November 11, 2003

Examiner: Tran, Binh X, Group Art Unit: 1765

Conf. No.: 7748

Title: SELECTIVE ETCH PROCESS OF A SACRIFICIAL LIGHT ABSORBING

MATERIAL (SLAM) OVER A DIELECTRIC MATERIAL

Mail Stop: AMENDMENT Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL RESPONSE TO OFFICE ACTION DATED JULY 18, 2006

SIR:

In response to the Office Action dated July 18, 2006, having a shortened statutory period for response expired on October 18, 2006, please enter this Supplemental Response and reconsider the pending application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 50-3562, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.